

=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 50 S L3 SSS SAM
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 39 S L7 SSS SAM
L9 SCREEN 970 AND 2067
L10 STRUCTURE UPLOADED
L11 QUE L10 AND L9
L12 19 S L11 SSS SAM
L13 102 S L4 OR L8 OR L12

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004

L14 238 S L13
L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)
L16 301 S OXIME SULFONATE
L17 3 S L16 AND L14
L18 9 S L14 AND (RESIST OR PHOTORESIST)
L19 6 S L18 NOT L17

=> screen 970 AND 2067

L5 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10642576-2.str

L6 STRUCTURE UPLOADED

=> que L6 AND L5

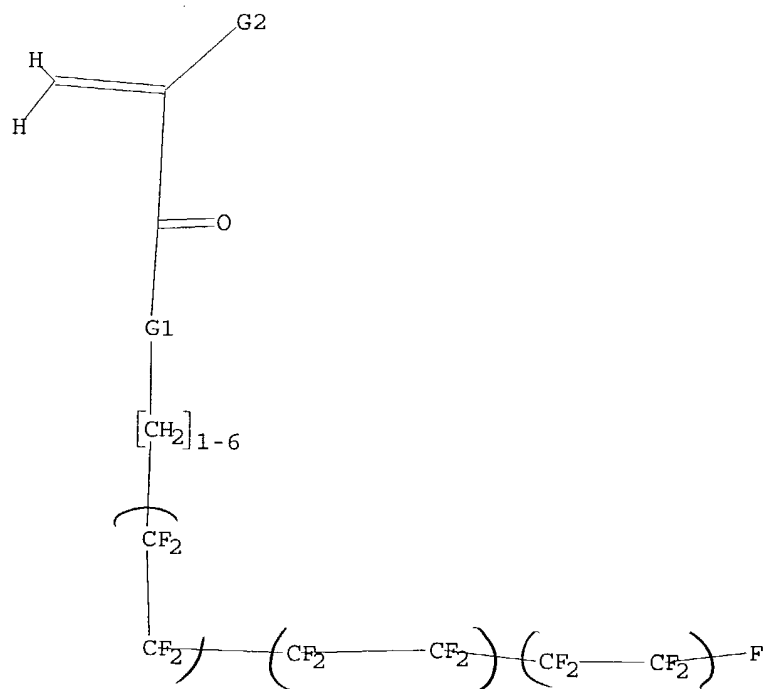
L7 QUE L6 AND L5

=> d

L7 HAS NO ANSWERS

L5 SCR 970 AND 2067

L6 STR



q = 3

G1 O,S,N

G2 CH₂,H

Structure attributes must be viewed using STN Express query preparation.

L7 QUE ABB=ON PLU=ON L6 AND L5

=> s 17 sss sam

SAMPLE SEARCH INITIATED 20:40:33 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 415 TO ITERATE

100.0% PROCESSED 415 ITERATIONS

SEARCH TIME: 00.00.01

39 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 7078 TO 9522

PROJECTED ANSWERS: 406 TO 1154

L8 39 SEA SSS SAM L6 AND L5
=>Testing the current file.... screen
ENTER SCREEN EXPRESSION OR (END):end

=> screen 970 AND 2067

L9 SCREEN CREATED

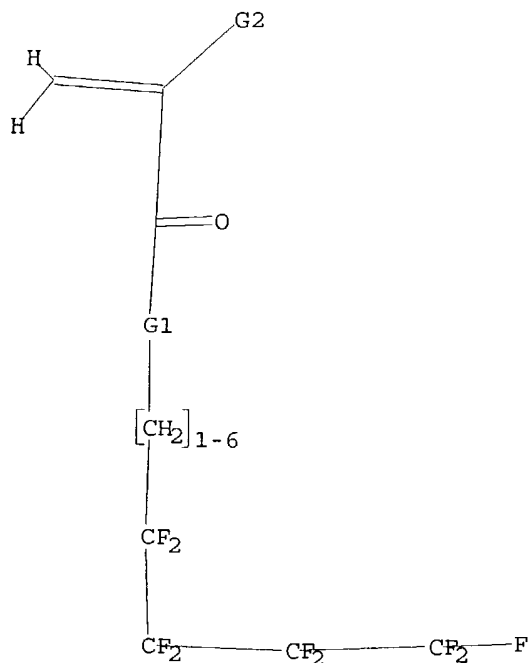
=>
Uploading C:\Program Files\Stnexp\Queries\10642576-1.str

L10 STRUCTURE UPLOADED

=> que L10 AND L9

L11 QUE L10 AND L9

=> d
L11 HAS NO ANSWERS
L9 SCR 970 AND 2067
L10 STR

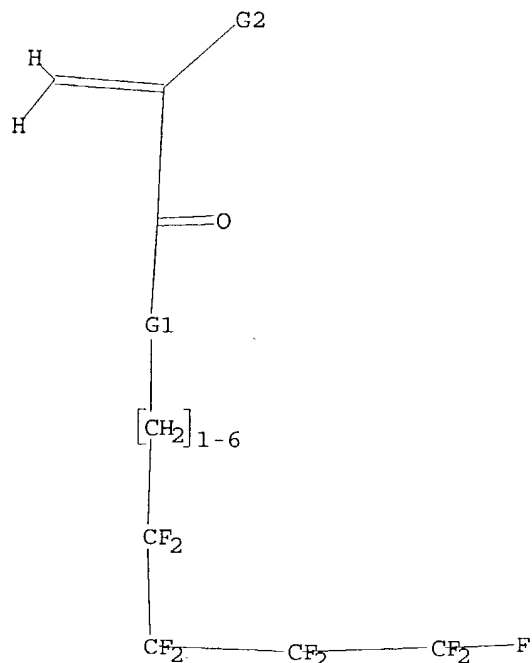


G1 O,S,N
G2 CH₂,H

q=2

Structure attributes must be viewed using STN Express query preparation.
L11 QUE ABB=ON PLU=ON L10 AND L9

=> d
L11 HAS NO ANSWERS
L9 SCR 970 AND 2067
L10 STR



g=2

G1 O,S,N
G2 CH2,H

Structure attributes must be viewed using STN Express query preparation.
L11 QUE ABB=ON PLU=ON L10 AND L9

=> s l11 sss sam
SAMPLE SEARCH INITIATED 20:41:17 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 458 TO ITERATE

100.0% PROCESSED 458 ITERATIONS 19 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 7877 TO 10443
PROJECTED ANSWERS: 119 TO 641

L12 19 SEA SSS SAM L10 AND L9

=> d his

(FILE 'HOME' ENTERED AT 20:39:16 ON 17 SEP 2004)

FILE 'REGISTRY' ENTERED AT 20:39:30 ON 17 SEP 2004

L1 SCREEN 970 AND 2067
L2 STRUCTURE UPLOADED
L3 QUE L2 AND L1
L4 50 S L3 SSS SAM
L5 SCREEN 970 AND 2067
L6 STRUCTURE UPLOADED
L7 QUE L6 AND L5
L8 39 S L7 SSS SAM
L9 SCREEN 970 AND 2067
L10 STRUCTURE UPLOADED

=> screen 970 AND 2067

L1 SCREEN CREATED

=>

Uploading C:\Program Files\Stnexp\Queries\10642576-3.str

L2 STRUCTURE UPLOADED

=> que L2 AND L1

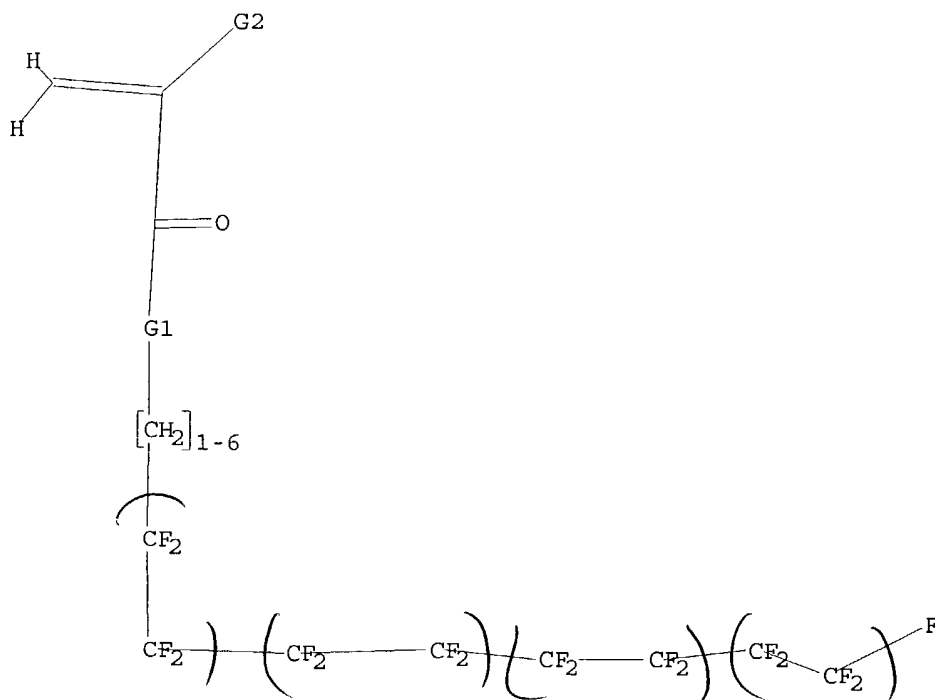
L3 QUE L2 AND L1

=> d

L3 HAS NO ANSWERS

L1 SCR 970 AND 2067

L2 STR



G1 O,S,N

G2 CH2,H

Structure attributes must be viewed using STN Express query preparation.

L3 QUE ABB=ON PLU=ON L2 AND L1

=> s 13

SAMPLE SEARCH INITIATED 20:48:59 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 350 TO ITERATE

100.0% PROCESSED 350 ITERATIONS

50 ANSWERS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**

PROJECTED ITERATIONS: 5878 TO 8122

PROJECTED ANSWERS: 2990 TO 4648

L4 50 SEA SSS SAM L2 AND L1

L11 QUE L10 AND L9
L12 19 S L11 SSS SAM

=> s 14 or 18 or 112
L13 102 L4 OR L8 OR L12

=> FIL HCAPLUS, CAPLUS, USPATFULL
COST IN U.S. DOLLARS

	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	1.68	1.89

FILE 'HCAPLUS' ENTERED AT 20:41:37 ON 17 SEP 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 20:41:37 ON 17 SEP 2004
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 20:41:37 ON 17 SEP 2004
CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 113
L14 238 L13

=> duplicates remove 114
DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n
PROCESSING COMPLETED FOR L14
L15 130 DUPLICATE REMOVE L14 (108 DUPLICATES REMOVED)

=> s oxime sulfonate
L16 301 OXIME SULFONATE

=> s 116 and 114
L17 3 L16 AND L14

=> d 117 1-3 ibib hitstr

L17 ANSWER 1 OF 3 HCAPLUS COPYRIGHT 2004 ACS on STN
ACCESSION NUMBER: 2004:200910 HCAPLUS
DOCUMENT NUMBER: 140:243596
TITLE: Chemically amplified positive photoresists suppressing
development defects
INVENTOR(S): Momota, Atsushi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

*present
invention*

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004078105	A2	20040311	JP 2002-241946	20020822
US 2004048190	A1	20040311	US 2003-642576	20030819
PRIORITY APPLN. INFO.:			JP 2002-241946	A 20020822
OTHER SOURCE(S):	MARPAT	140:243596		
IT 668476-75-3P				
RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM				

(Technical or engineered material use); PREP (Preparation); USES (Uses)
 (surfactants; chemical amplified pos. photoresists containing fluoroalkyl
 acrylate-polymerized surfactants and suppressing development defects)

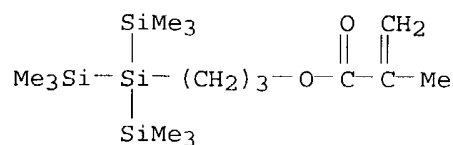
RN 668476-75-3 HCAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with
 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate,
 α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-1,2-
 ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-
 bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX
 NAME)

CM 1

CRN 114349-68-7

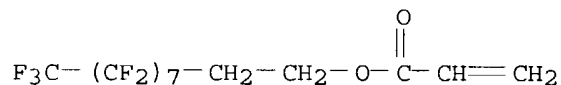
CMF C16 H38 O2 Si4



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

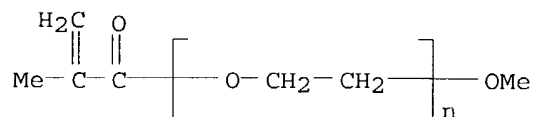


CM 3

CRN 26915-72-0

CMF (C2 H4 O)_n C5 H8 O2

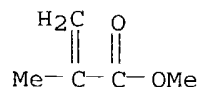
CCI PMS



CM 4

CRN 80-62-6

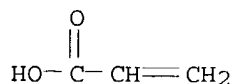
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



L17 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2004:200910 CAPLUS

DOCUMENT NUMBER: 140:243596

TITLE: Chemically amplified positive photoresists suppressing development defects

INVENTOR(S): Momota, Atsushi

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 69 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

present invention

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004078105	A2	20040311	JP 2002-241946	20020822
US 2004048190	A1	20040311	US 2003-642576	20030819
PRIORITY APPLN. INFO.:			JP 2002-241946	A 20020822

OTHER SOURCE(S): MARPAT 140:243596

IT **668476-75-3P**

RL: IMF (Industrial manufacture); MOA (Modifier or additive use); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

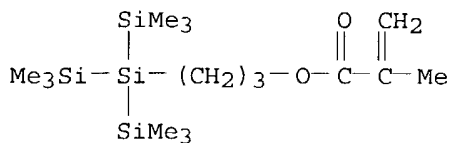
RN 668476-75-3 CAPLUS

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate, α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 114349-68-7

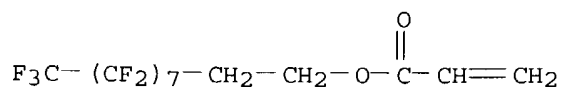
CMF C16 H38 O2 Si4



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

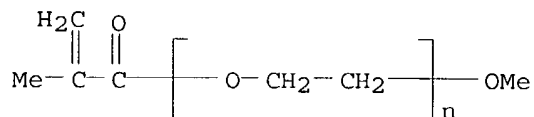


CM 3

CRN 26915-72-0

CMF (C2 H4 O)n C5 H8 O2

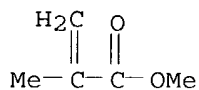
CCI PMS



CM 4

CRN 80-62-6

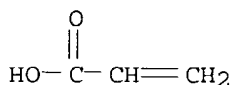
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



L17 ANSWER 3 OF 3 USPATFULL on STN

ACCESSION NUMBER: 2004:63672 USPATFULL

TITLE: Positive photoresist composition

INVENTOR(S): Momota, Makoto, Shizuoka, JAPAN

PATENT ASSIGNEE(S): FUJI PHOTO FILM CO., LTD. (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2004048190	A1	20040311
APPLICATION INFO.:	US 2003-642576	A1	20030819 (10)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 2002-241946	20020822
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	SUGHRUE MION, PLLC, 2100 PENNSYLVANIA AVENUE, N.W.,	

present invention

WASHINGTON, DC, 20037

NUMBER OF CLAIMS: 8

EXEMPLARY CLAIM: 1

LINE COUNT: 1349

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 668476-75-3P

(surfactants; chemical amplified pos. photoresists containing fluoroalkyl acrylate-polymerized surfactants and suppressing development defects)

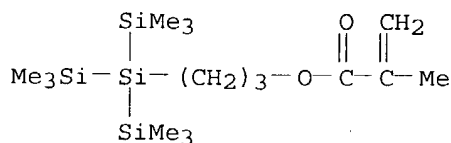
RN 668476-75-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, methyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl 2-propenoate, α -(2-methyl-1-oxo-2-propenyl)- ω -methoxypoly(oxy-1,2-ethanediyl), 2-propenoic acid and 3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 114349-68-7

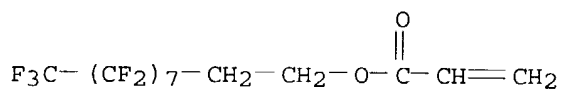
CMF C16 H38 O2 Si4



CM 2

CRN 27905-45-9

CMF C13 H7 F17 O2

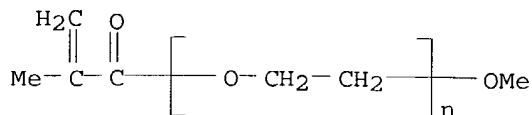


CM 3

CRN 26915-72-0

CMF (C2 H4 O)_n C5 H8 O2

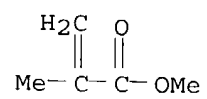
CCI PMS



CM 4

CRN 80-62-6

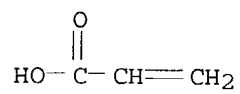
CMF C5 H8 O2



CM 5

CRN 79-10-7

CMF C3 H4 O2



L19 ANSWER 1 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 2003:735196 HCAPLUS

DOCUMENT NUMBER: 139:267983

TITLE: Positive-working **photoresist** composition
containing polymer with fluoro-aliphatic group

INVENTOR(S): Fujimori, Toru

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003262952	A2	20030919	JP 2002-65444	20020311
PRIORITY APPLN. INFO.:			JP 2002-65444	20020311

IT **602299-35-4**

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(surfactant; pos. **photoresist** composition containing polymer with fluoro-aliphatic group)

RN 602299-35-4 HCAPLUS

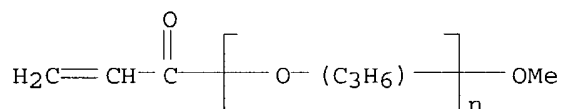
CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl ester, polymer with α -(1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl) and α -(1-oxo-2-propenyl)- ω -methoxypoly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

CM 1

CRN 83844-54-6

CMF (C3 H6 O)_n C4 H6 O2

CCI IDS, PMS

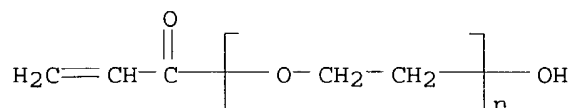


CM 2

CRN 26403-58-7

CMF (C2 H4 O)_n C3 H4 O2

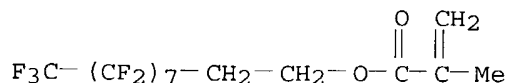
CCI PMS



CM 3

CRN 1996-88-9

CMF C14 H9 F17 O2



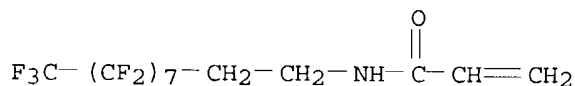
L19 ANSWER 2 OF 6 HCAPLUS COPYRIGHT 2004 ACS on STN
 ACCESSION NUMBER: 1998:335551 HCAPLUS
 DOCUMENT NUMBER: 129:54119
 TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their (polymer) films, and **photoresists** using the same
 INVENTOR(S): Miyashita, Tokuji
 PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji
 SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10139747	A2	19980526	JP 1996-312953	19961108
PRIORITY APPLN. INFO.:			JP 1996-312953	19961108
OTHER SOURCE(S):			MARPAT 129:54119	

IT **208589-71-3P**
 RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (LB films of N-polyfluoroalkyl(meth)acrylamides and their polymers with good water repellency, photosensitivity, and slip property)
 RN 208589-71-3 HCAPLUS
 CN 2-Propenamide, N-(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl)-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 208589-64-4
 CMF C13 H8 F17 N O



L19 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN
 ACCESSION NUMBER: 2003:735196 CAPLUS
 DOCUMENT NUMBER: 139:267983
 TITLE: Positive-working **photoresist** composition containing polymer with fluoro-aliphatic group
 INVENTOR(S): Fujimori, Toru
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 88 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2003262952	A2	20030919	JP 2002-65444	20020311
PRIORITY APPLN. INFO.:			JP 2002-65444	20020311

IT 602299-35-4

RL: MOA (Modifier or additive use); TEM (Technical or engineered material use); USES (Uses)

(surfactant; pos. **photoresist** composition containing polymer with fluoro-aliphatic group)

RN 602299-35-4 CAPLUS

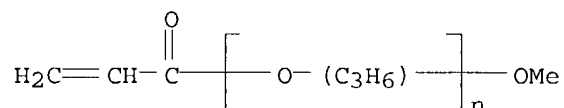
CN 2-Propenoic acid, 2-methyl-, 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl ester, polymer with α -(1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl) and α -(1-oxo-2-propenyl)- ω -methoxypoly[oxy(methyl-1,2-ethanediyl)] (9CI) (CA INDEX NAME)

CM 1

CRN 83844-54-6

CMF (C3 H6 O)_n C4 H6 O2

CCI IDS, PMS

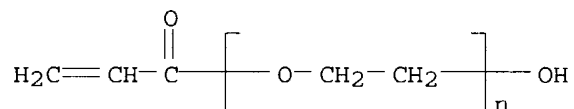


CM 2

CRN 26403-58-7

CMF (C2 H4 O)_n C3 H4 O2

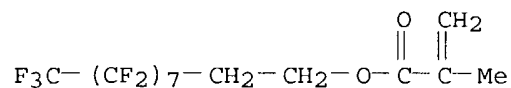
CCI PMS



CM 3

CRN 1996-88-9

CMF C14 H9 F17 O2



L19 ANSWER 4 OF 6 CAPLUS COPYRIGHT 2004 ACS on STN

ACCESSION NUMBER: 1998:335551 CAPLUS

DOCUMENT NUMBER: 129:54119

TITLE: N-Polyfluoroalkyl-substituted (meth)acrylamides, their (polymer) films, and **photoresists** using the same

INVENTOR(S): Miyashita, Tokuji

PATENT ASSIGNEE(S): Chisso Corp., Japan; Miyashita, Tokuji

SOURCE: Jpn. Kokai Tokkyo Koho, 11 pp.

DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

CODEN: JKXXAF

duplicate

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10139747	A2	19980526	JP 1996-312953	19961108
PRIORITY APPLN. INFO.:			JP 1996-312953	19961108
OTHER SOURCE(S):	MARPAT 129:54119			

IT 208589-71-3P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(LB films of N-polyfluoroalkyl(meth)acrylamides and their polymers with good water repellency, photosensitivity, and slip property)

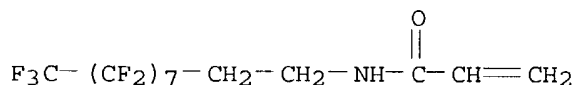
RN 208589-71-3 CAPLUS

CN 2-Propenamide, N-(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl)-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 208589-64-4

CMF C13 H8 F17 N O



L19 ANSWER 5 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:59638 USPATFULL

TITLE: Top coating for synthetic leathers

INVENTOR(S): Huang, Hsu-Nan, Newark, DE, UNITED STATES

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 2002033468	A1	20020321
APPLICATION INFO.:	US 2001-970478	A1	20011004 (9)
RELATED APPLN. INFO.:	Division of Ser. No. US 2000-495132, filed on 31 Jan 2000, PENDING		

	NUMBER	DATE
PRIORITY INFORMATION:	US 1999-123601P	19990310 (60)
DOCUMENT TYPE:	Utility	
FILE SEGMENT:	APPLICATION	
LEGAL REPRESENTATIVE:	E I DU PONT DE NEMOURS AND COMPANY, LEGAL DEPARTMENT - PATENTS, 1007 MARKET STREET, WILMINGTON, DE, 19898	
NUMBER OF CLAIMS:	11	
EXEMPLARY CLAIM:	1	
LINE COUNT:	1042	

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 292849-59-3P

(water- and oil-repellent coating compns. for synthetic grain leather)

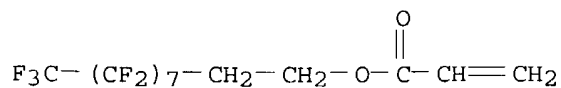
RN 292849-59-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with 3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptafluorodecyl 2-propenoate, N-(hydroxymethyl)-2-propenamide and α -(2-methyl-1-oxo-2-propenyl)- ω -hydroxypoly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

CMF C13 H7 F17 O2

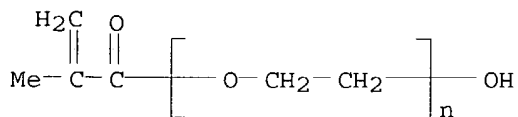


CM 2

CRN 25736-86-1

CMF (C2 H4 O)_n C4 H6 O2

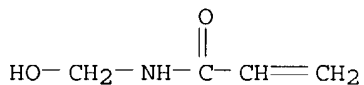
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CM 3

CRN 924-42-5

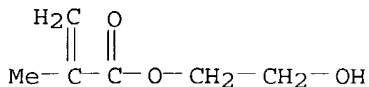
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CM 4

CRN 868-77-9

CMF C6 H10 O3



L19 ANSWER 6 OF 6 USPATFULL on STN

ACCESSION NUMBER: 2002:45669 USPATFULL

TITLE: Top coating for synthetic leathers

INVENTOR(S): Huang, Hsu-Nan, Newark, DE, United States

PATENT ASSIGNEE(S): E. I. du Pont de Nemours and Company, Wilmington, DE, United States (U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6353051	B1	20020305
APPLICATION INFO.:	US 2000-495132		20000131 (9)

NUMBER	DATE
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PRIORITY INFORMATION: US 1999-123601P 19990310 (60)
DOCUMENT TYPE: Utility
FILE SEGMENT: GRANTED
PRIMARY EXAMINER: Yoon, Tae H.
NUMBER OF CLAIMS: 9
EXEMPLARY CLAIM: 1
NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)
LINE COUNT: 1019

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 292849-59-3P

(water- and oil-repellent coating compns. for synthetic grain leather)

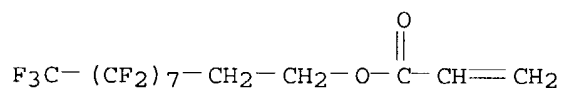
RN 292849-59-3 USPATFULL

CN 2-Propenoic acid, 2-methyl-, 2-hydroxyethyl ester, polymer with
3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10-heptafluorodecyl 2-propenoate,
N-(hydroxymethyl)-2-propenamide and α -(2-methyl-1-oxo-2-propenyl)-
 ω -hydroxypoly(oxy-1,2-ethanediyl), graft (9CI) (CA INDEX NAME)

CM 1

CRN 27905-45-9

CMF C13 H7 F17 O2

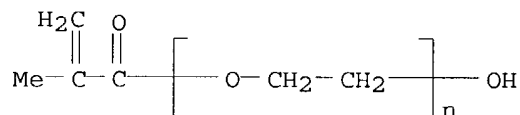


CM 2

CRN 25736-86-1

CMF (C2 H4 O)_n C4 H6 O2

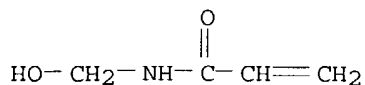
CCI PMS



CM 3

CRN 924-42-5

CMF C4 H7 N O2



CM 4

CRN 868-77-9

CMF C6 H10 O3

